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Patent Application No. 10/780,513
Customer Number: 42717

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Bor-Wen Chan, et al.	§	Docket No.:	TS03-485
		§		(24061.524)
Serial No.:	10/780,513	§	Examiner:	James M. Mitchell
		§		
Filing Date:	February 17, 2004	§	Art Unit:	2813
		§		
For:	Method to Form a Metal Silicide	§	Conf. No.:	1381
	Gate Device	§		
		§		

RESPONSE TO RESTRICTION REQUIREMENT

Mail Stop: Amendment
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450


Dear Sir:

In response to the Office Action mailed April 4, 2005, applicant hereby elects Group I, Claims 1-20, which is drawn to a method, classified in class 438, subclass 581.

Applicant's election is made with traverse on the grounds that the embodiments delineated by the examiner are not patentably distinct and therefore constitute a single invention concept.

An early action on the merits is respectfully requested.

Respectfully submitted,


David M. O'Dell
Reg. No. 42,044

Date: 4-15-05

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CERTIFICATE OF MAILING	
I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Mail Stop: Amendment, Commissioner For Patents, PO Box 1450, Alexandria, VA 22313-1450 on the date below.	
Name	<u>Bonnie Boyle</u>
Date	<u>4-15-05</u>